

EAST Search History

EAST Search History (Prior Art)

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S12	8403	(216/88,89).ccls. or (51/308,309).ccls. or (252/79.1).ccls.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/05/20 16:34
S13	1590	S12 and abrasive and ("cmp" or "chemical mechanical polishing" or (chemical adj mechanical adj polish\$3))	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/05/20 16:35
S14	530	S13 and ((colloidal near silica) same abrasive)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/05/20 16:35
S15	11	S14 and ((colloidal near silica) adj (size or span))	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/05/20 16:35
S16	0	S14 and ((colloidal near silica) adj span)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/05/20 16:37
S17	530	S14 and ((colloidal near silica) near\ span)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/05/20 16:37

S18	0	S14 and ((colloidal near silica) near span)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/05/20 16:37
S19	2	S14 and ((colloidal near silica) same span)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/05/20 16:37
S20	377	S14 and (particle adj (size or span))	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/05/20 16:46
S21	379	S14 and (particle near (size or span))	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/05/20 16:47
S22	3	S14 and (particle near span)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/05/20 16:47
S23	3	S14 and (particle adj span)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/05/20 16:47
S24	10	S20 and ("span value" or span)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/05/20 16:48
S25	10	S21 and ("span value" or span)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/05/20 16:48

S26	122	(chu adj "jia-ni").in. or (pryor adj james).in.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/05/20 17:16
S27	7	S26 and abrasive and ("cmp" or "chemical mechanical polishing" or (chemical adj mechanical adj polish\$3))	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/05/20 17:17
S28	21	S26 and (particle adj (size or span))	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/05/20 17:19
S29	2	S26 and ("span value" or span)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/05/20 17:20
S30	8	S26 and nanometer	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/05/20 17:27
S31	8	S26 and (nanometer or submicron)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/05/20 17:27

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